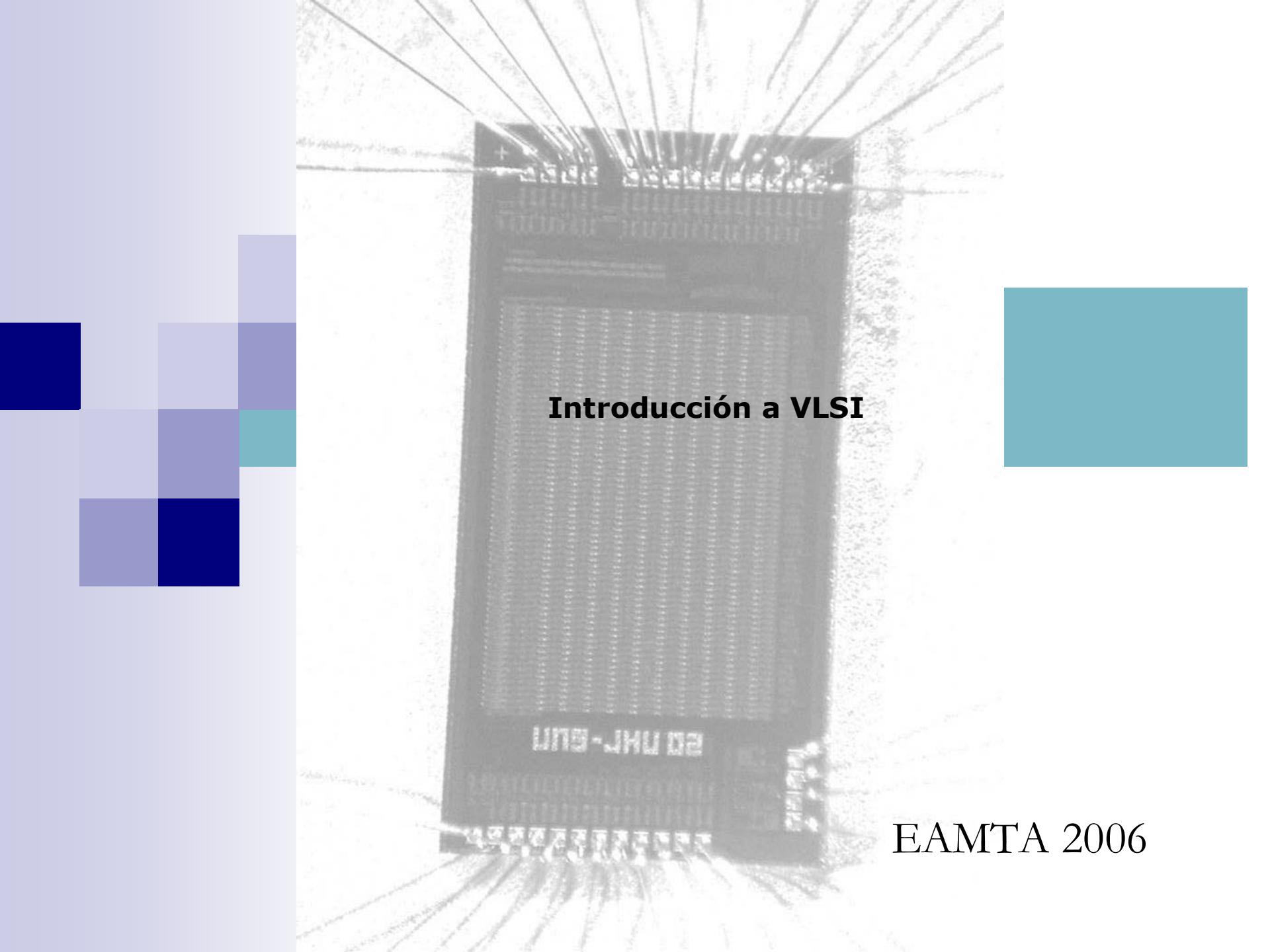


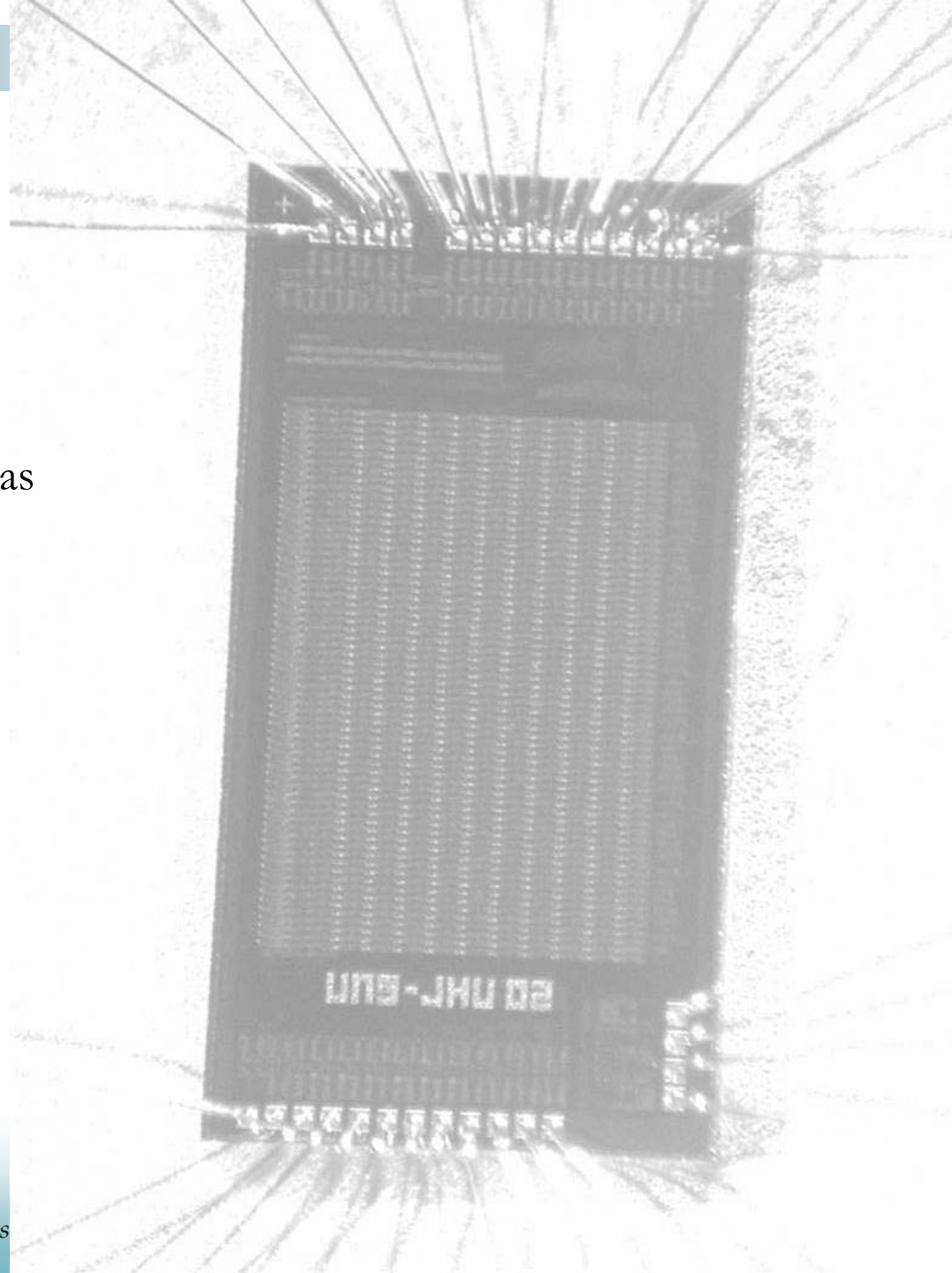
The background of the slide features a grayscale image of a VLSI (Very Large Scale Integration) chip. The chip is rectangular with a grid of pins along its top and bottom edges. Numerous thin wires are connected to these pins, radiating outwards. The chip itself has some text and a grid of small squares on its surface. Overlaid on the left side of the image is a decorative pattern of squares in various shades of blue and purple. On the right side, there is a solid teal square.

Introducción a VLSI

EAMTA 2006

Programa

- El Transistor MOS
- Layers y Layout
- Lógica Combinacional
- Lógica Secuencial y Subsistemas





Introducción a VLSI

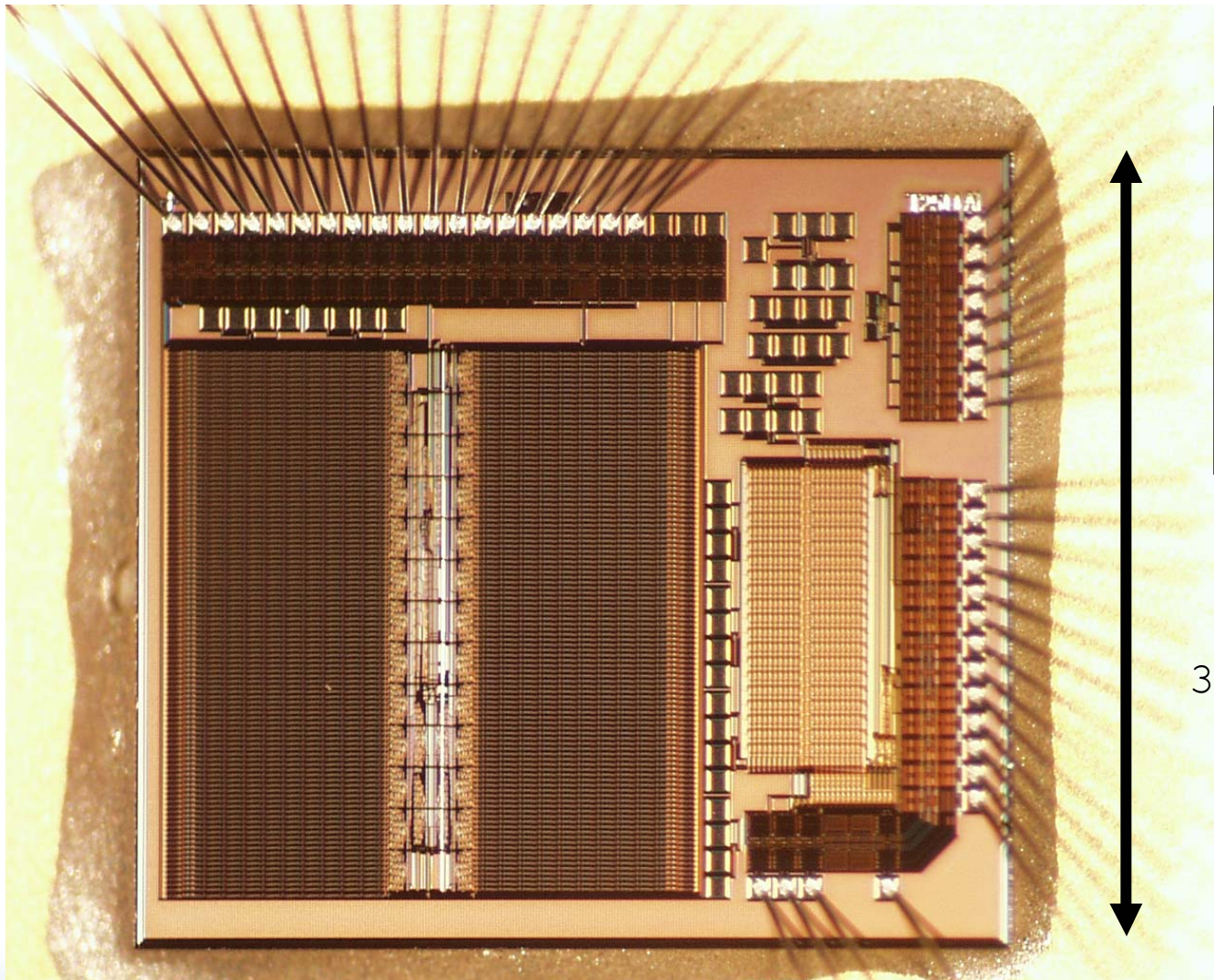
Clase 1: El transistor MOS

Organización

- Ejemplo de Motivación
- Modelo del transistor MOS
- El inversor CMOS
- El transistor como llave

Motivación

Ejemplo “autóctono”



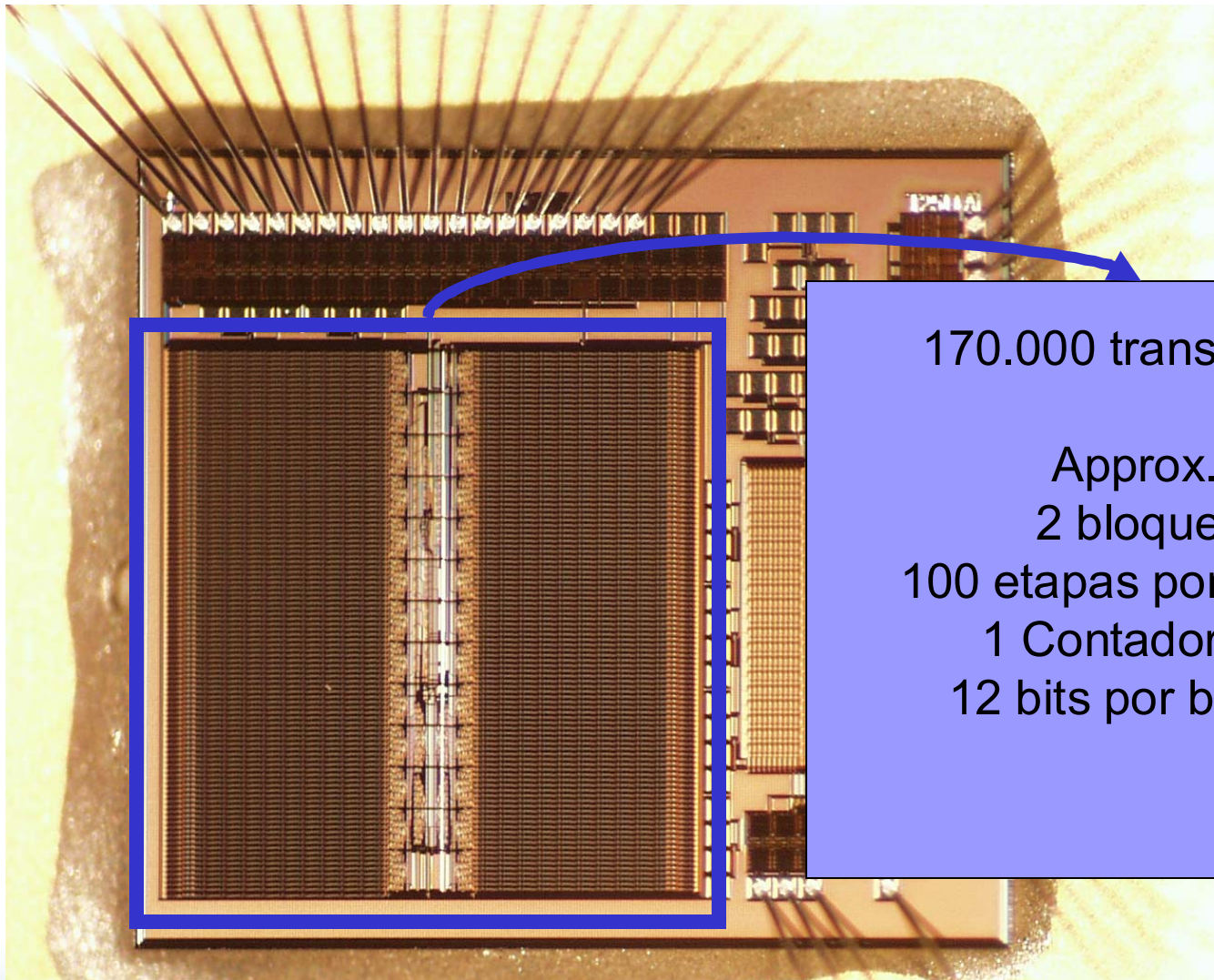
Tecnología

TSMC 0.35 μm

$\lambda = 0.2 \mu\text{m}$

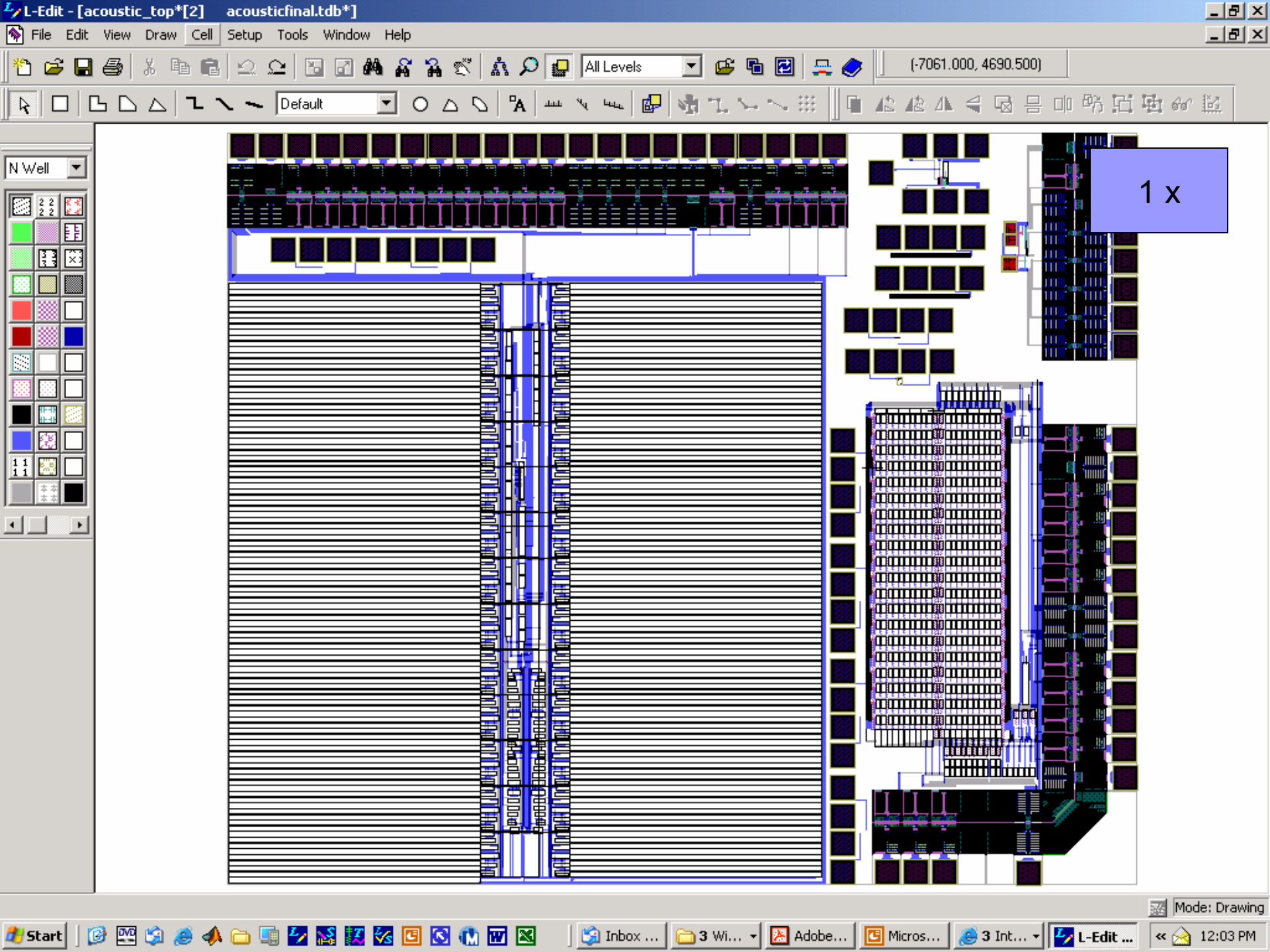
3 mm

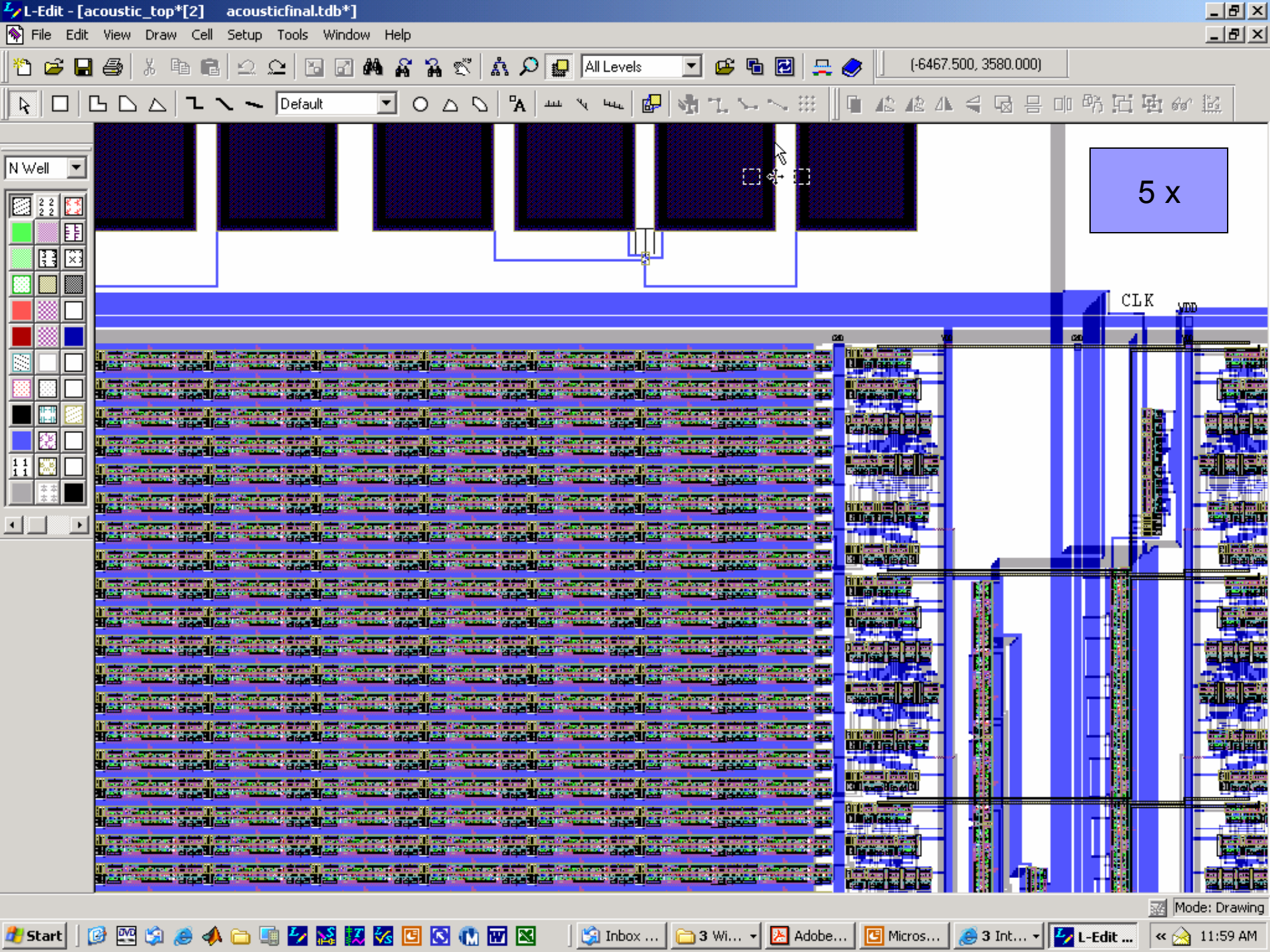
Ejemplo “autóctono” (2)

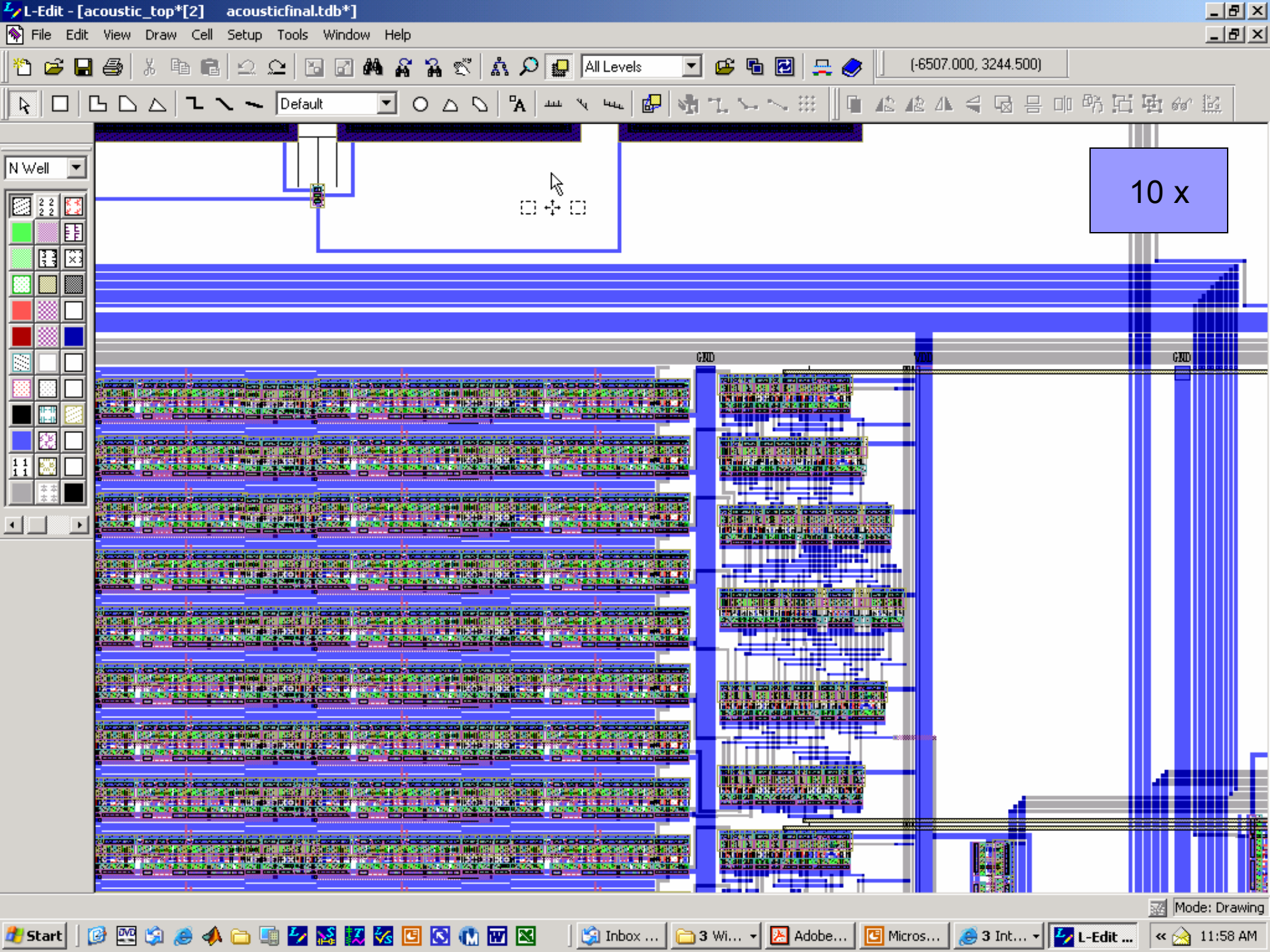


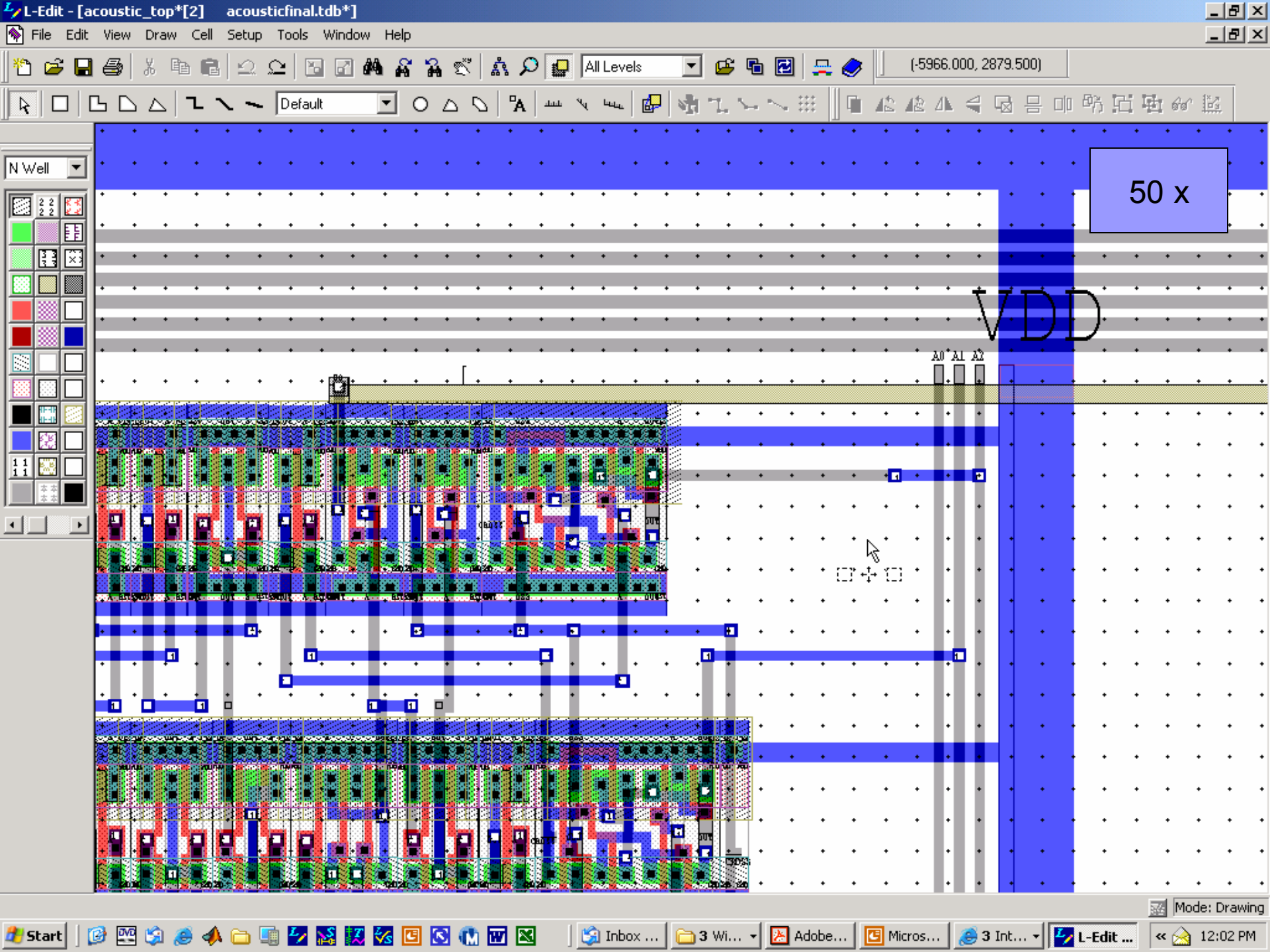
170.000 transistores

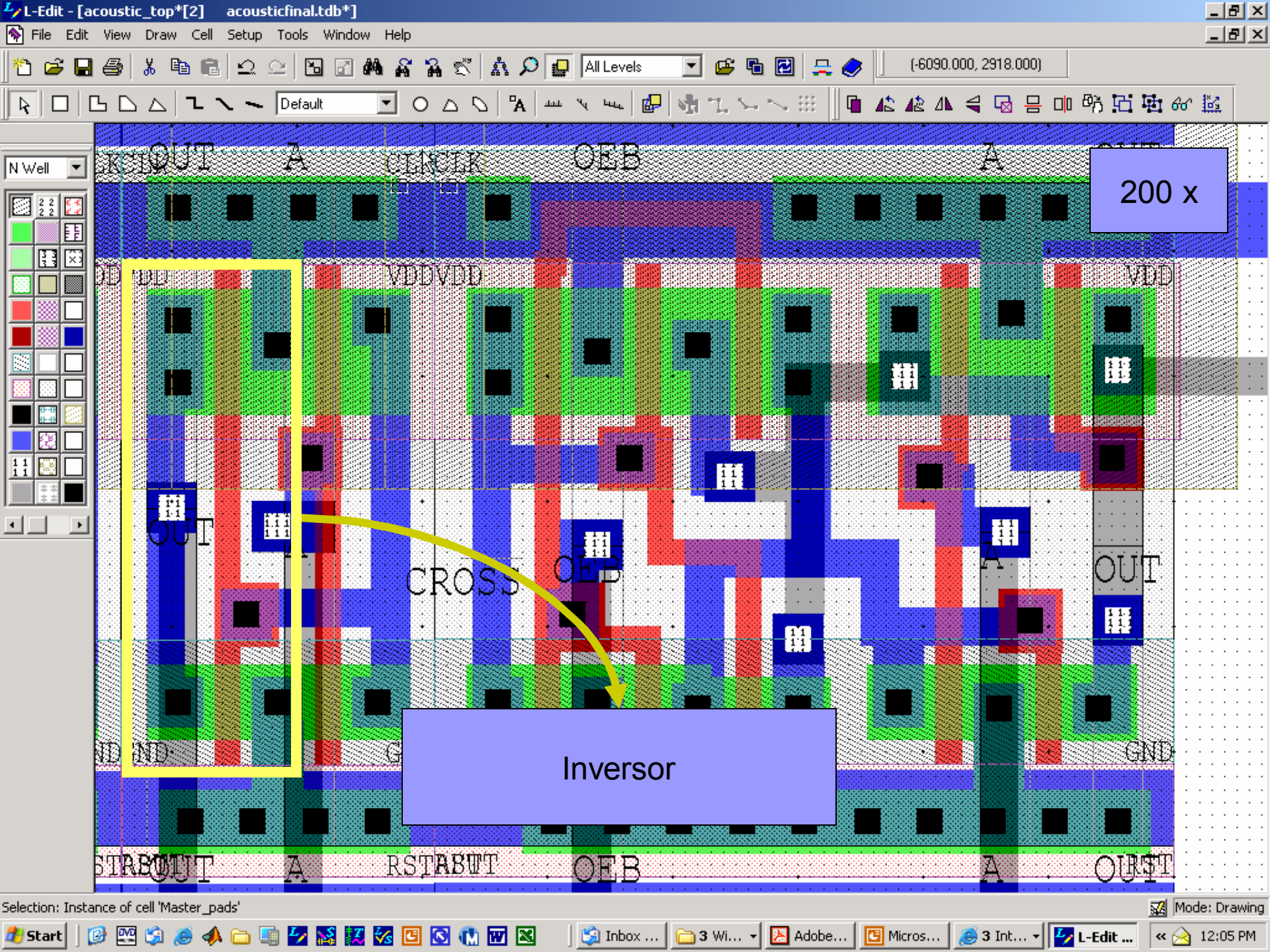
Approx.
2 bloques
100 etapas por bloque
1 Contador de
12 bits por bloque







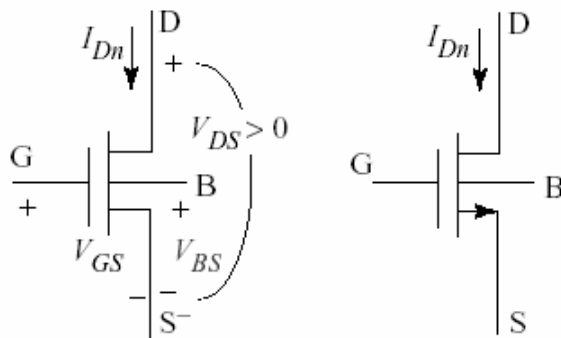




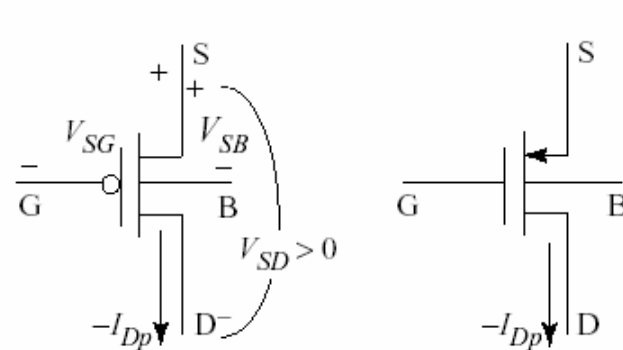
El transistor MOS

Transistores MOS

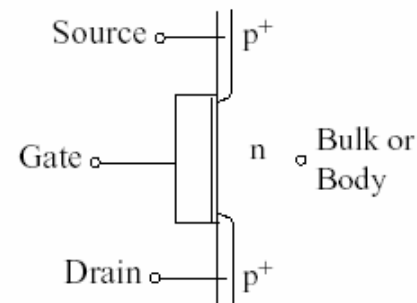
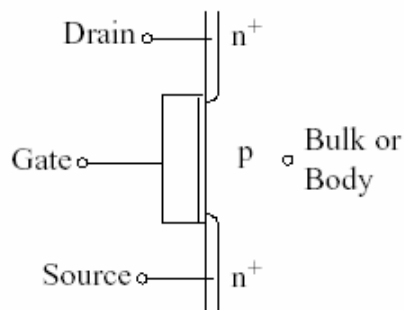
- Canal N (sobre sustrato P)
- Canal P (sobre sustrato N)



(a) n-channel MOSFET

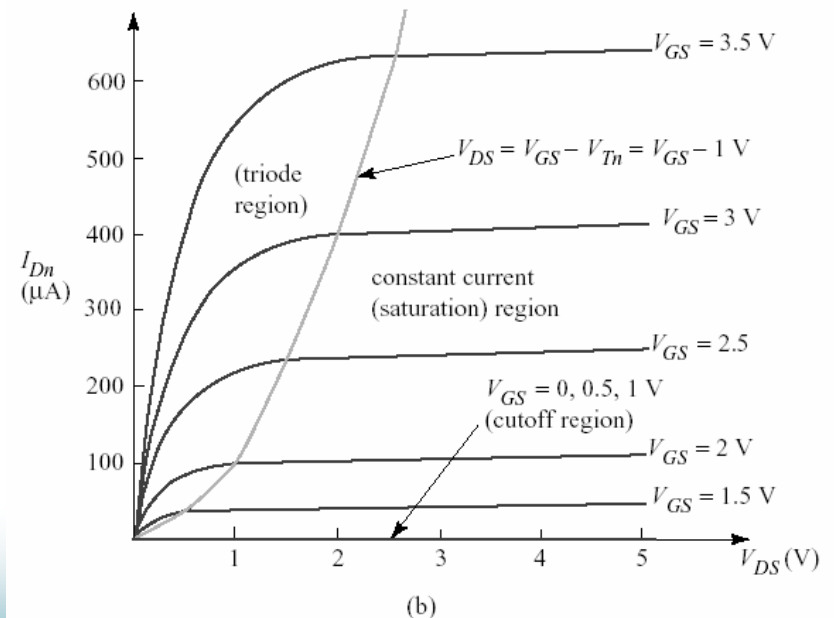
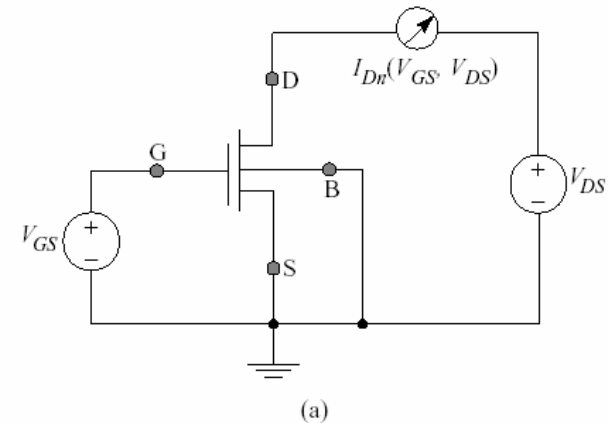


(b) p-channel MOSFET



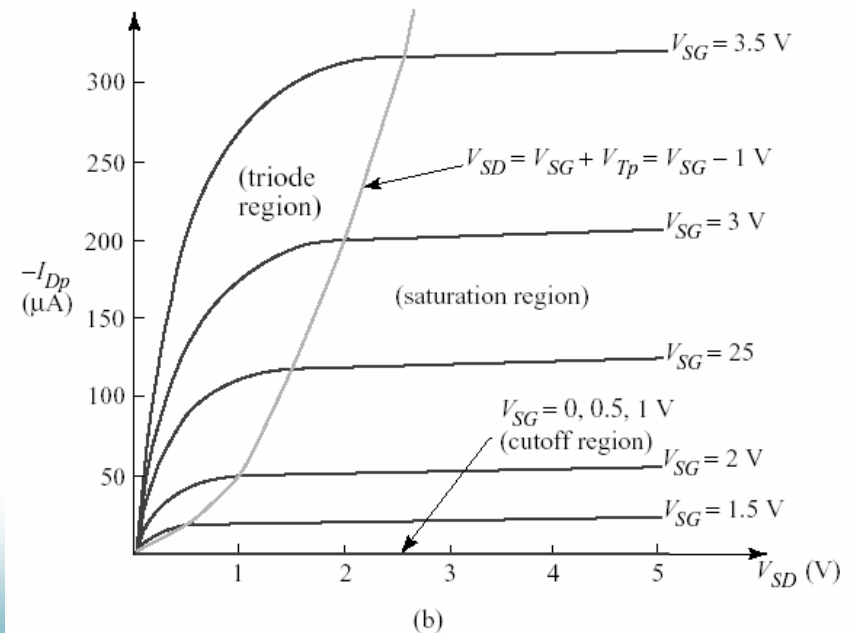
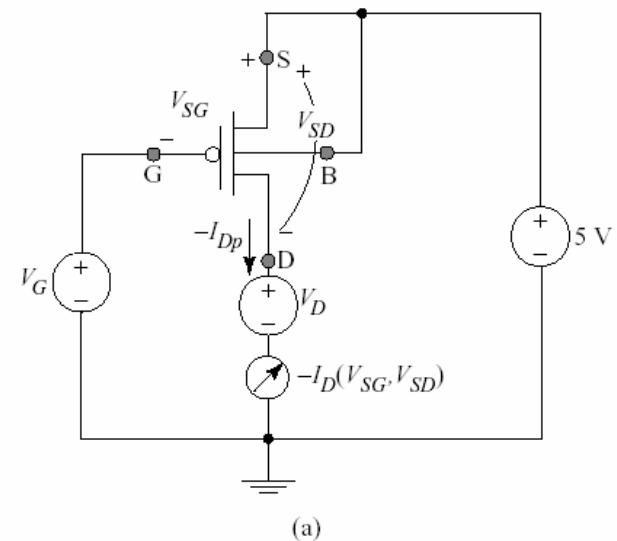
NMOS: Características de Drain

- $I_g = 0$
- $V_{db} = V_{ds} > 0$ para que la juntura drain-bulk esté en inversa
- Medición:
 - Bulk a tierra (dispositivo de tres terminales)
 - Se fija V_g
 - Se varía V_{ds} y se mide I_d



PMOS: Características de drain

- $I_g=0$
- $V_{db}=V_{ds} < 0$ para que la juntura drain-bulk esté en inversa
- Medición:
 - Bulk a V_{dd} (dispositivo de tres terminales)
 - Se fija V_g
 - Se varía V_{ds} y se mide I_d

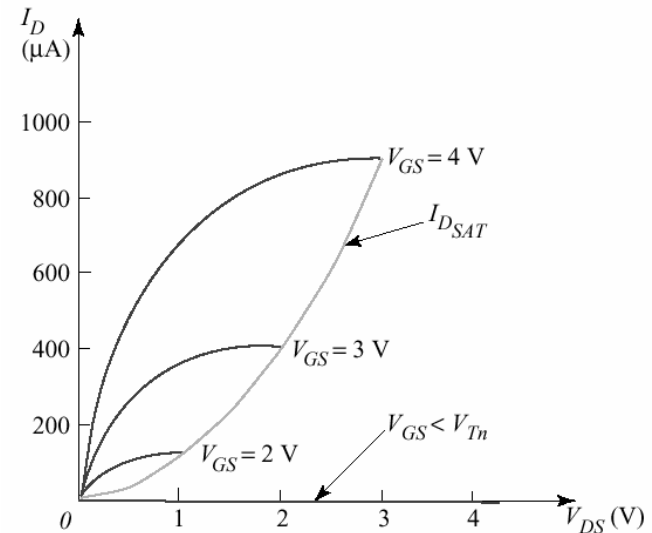


Regiones de trabajo

- Triodo: I_D varía con V_{DS} y V_{GS}

$$I_D = \mu_n C_{ox} \left(\frac{W}{L} \right) (V_{GS} - V_{Tn} - V_{DS}/2) V_{DS}$$

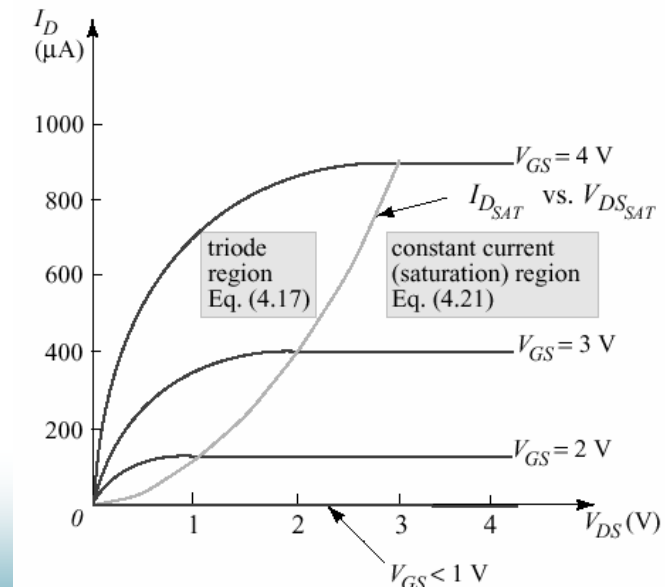
$$V_{GS} - V_{DS} > V_{Tn} \text{ and } V_{GS} > V_{Tn}.$$



- Saturación: I_D permanece fija con respecto a V_{DS}

$$I_D = I_{D(sat)} = \mu_n C_{ox} \left(\frac{W}{2L} \right) (V_{GS} - V_{Tn})^2$$

$$V_{GS} > V_{Tn} \text{ and } V_{DS} > V_{DS(sat)} = V_{GS} - V_{Tn},$$

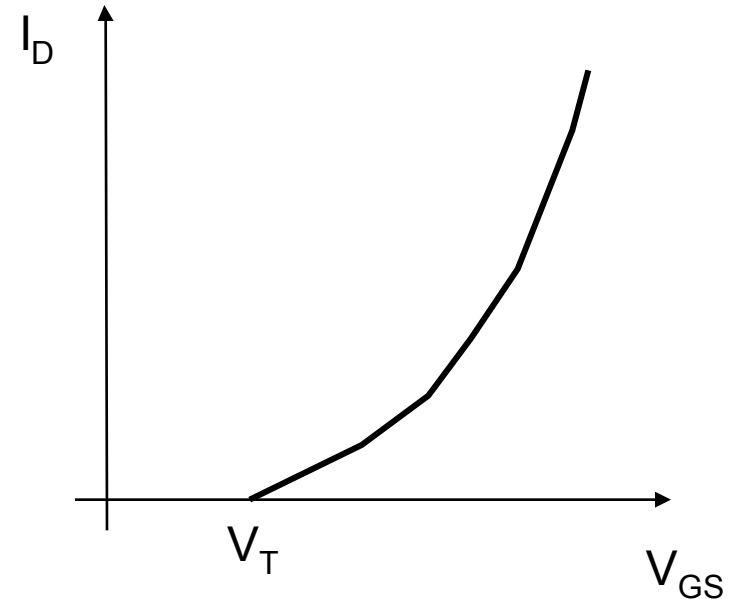


NMOS Transfer curve (I_D vs. V_{GS})

- Se supone al transistor trabajando en saturación

$$I_D = I_{D(sat)} = \mu_n C_{ox} \left(\frac{W}{2L} \right) (V_{GS} - V_{Tn})^2$$

- Para el proceso AMI 0.5 (*)
 - $K'_n = (U_0 \cdot C_{ox} / 2) = 55.1 \text{ uA/V}^2$
 - $V_{gsn} = 0.75 \text{ V}$
 - Si $W_n = 10 \text{ um}$, $L_n = 2 \text{ um}$, $V_{gs} = 5 \text{ V}$
 - $I_D = (55 \text{e-}6) \cdot (10/2) \cdot (5 - 0.75)^2 = 4.96 \text{ mA}$



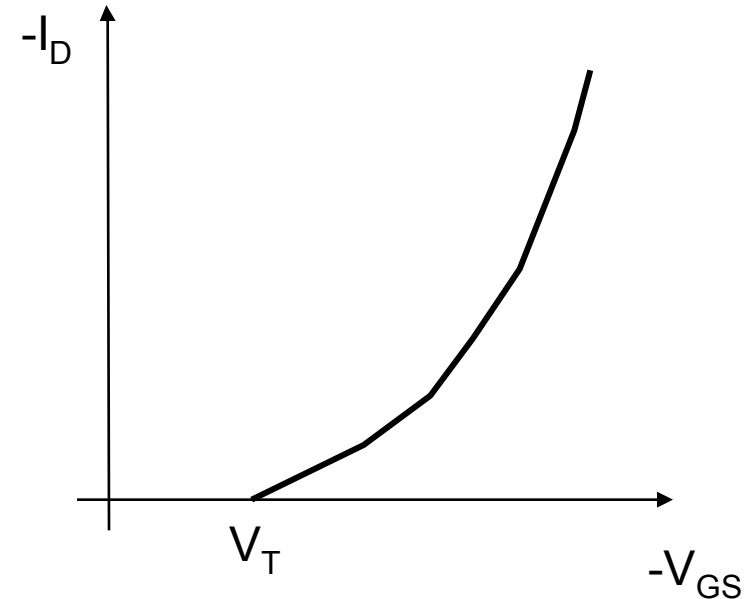
(*) <http://www.mosis.org/cgi-bin/cgiwrap/umosis/swp/params/ami-c5/t62r-params.txt>

PMOS Transfer curve (I_D vs. V_{GS})

- Se supone al transistor trabajando en saturación

$$I_D = I_{D(sat)} = -\mu_n C_{ox} \left(\frac{W}{2L} \right) (V_{GS} - V_{Tn})^2$$

- Para el proceso AMI 0.5 (*)
 - $K'_p = (U_o * C_{ox} / 2) = 18.5 \mu A / V^2$
 - $V_{gsp} = -0.93V$
 - Si $W_p = 10\mu m$, $L_p = 2\mu m$, $V_{GS} = -5V$
 - $I_D = -18.5e-6 * (10/2) * (-5 + 0.93)^2 = -1.50 \text{ mA}$



(*) <http://www.mosis.org/cgi-bin/cgiwrap/umosis/swp/params/ami-c5/t62r-params.txt>

Características de salida

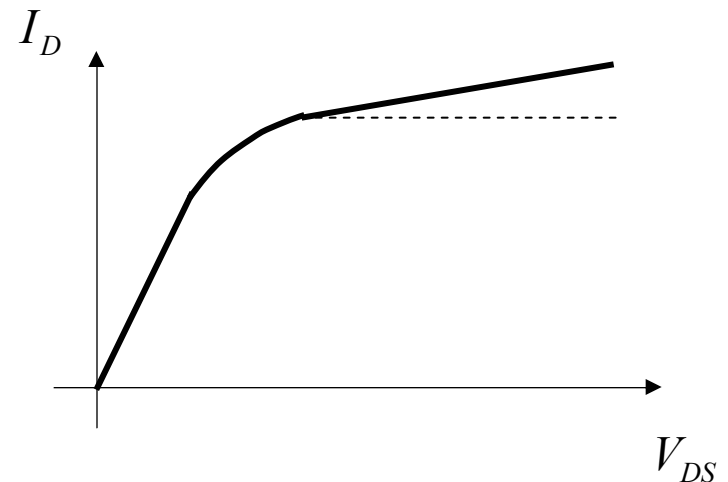
- Expresión corregida:

$$I_D = 1/2 \frac{W}{L} \mu_n C_{ox} (V_{gs} - V_t)^2 (1 + \lambda V_{DS})$$

- La impedancia de salida

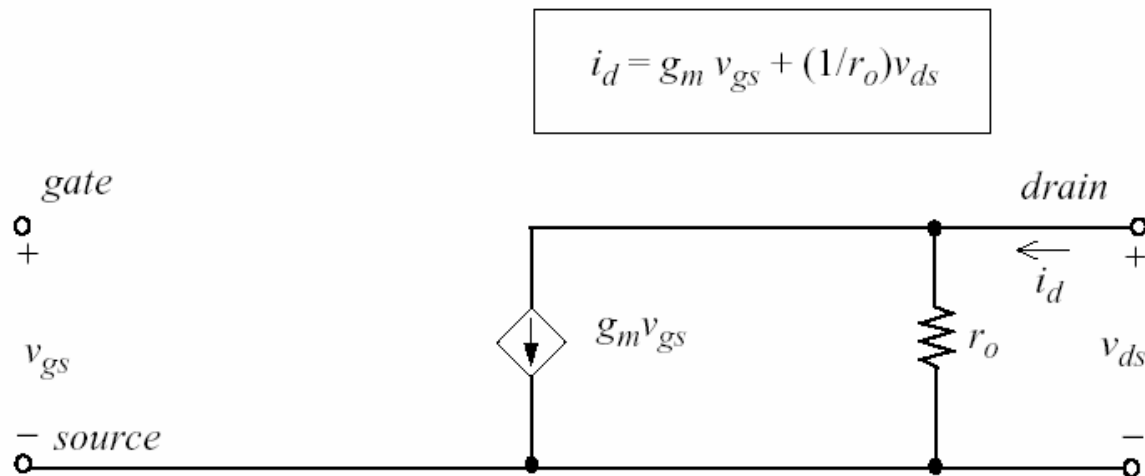
$$\frac{\partial I_D}{\partial v_{ds}} = \lambda I_D$$

$$\lambda = \frac{0.1}{L} [\mu m/V]$$



Cuanto más largo el canal mayor impedancia de salida

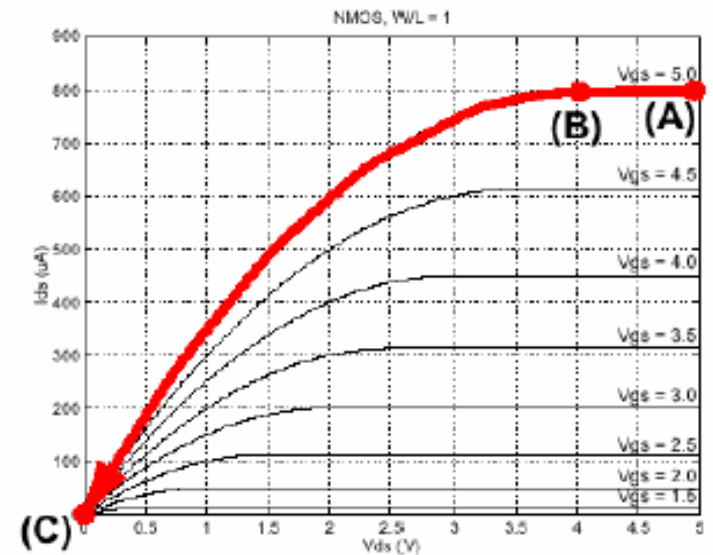
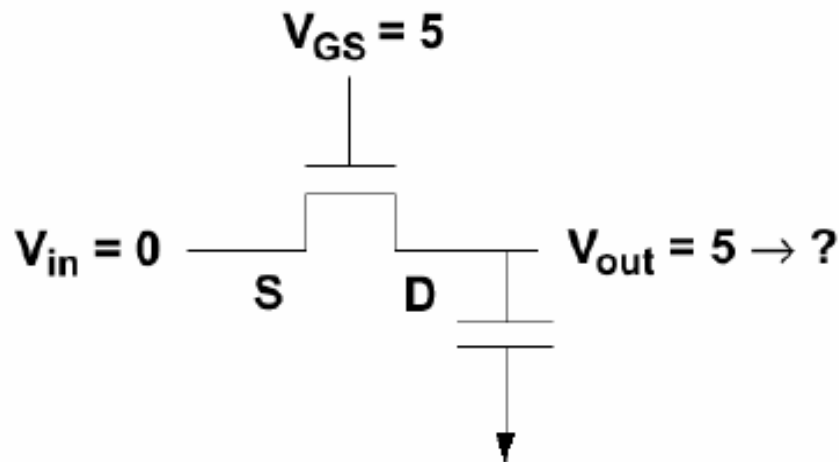
Modelo de pequeña señal



El transistor como llave

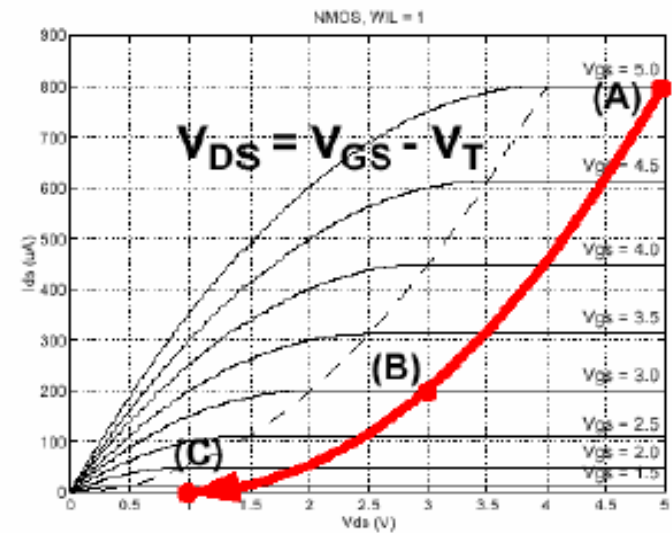
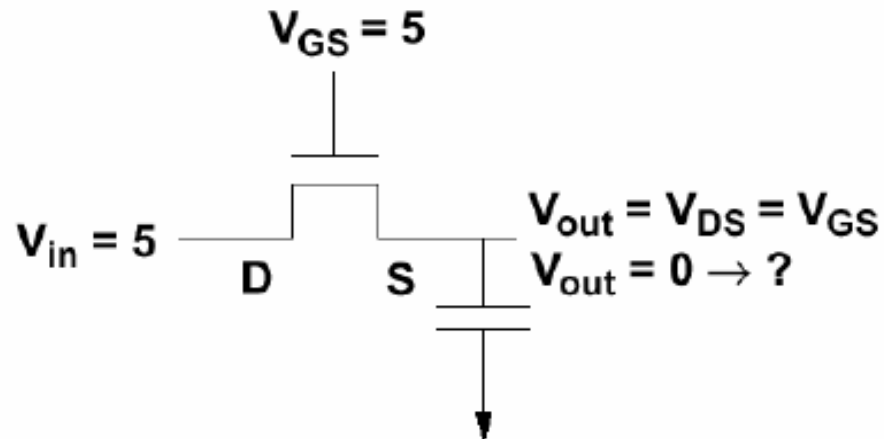
Switches

NMOS Pass Transistor—Passing 0

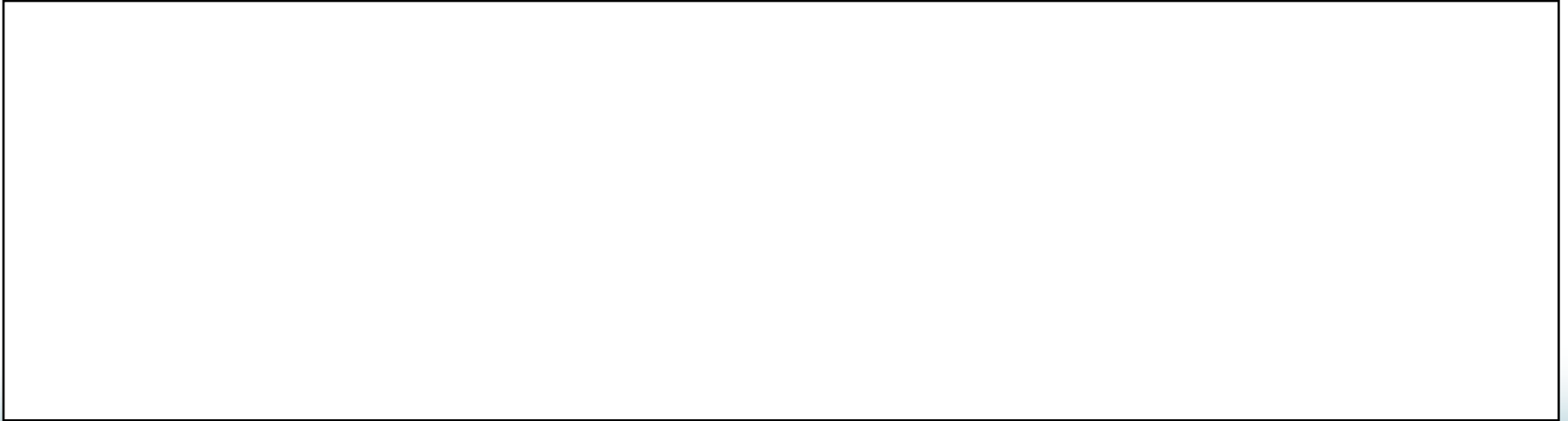
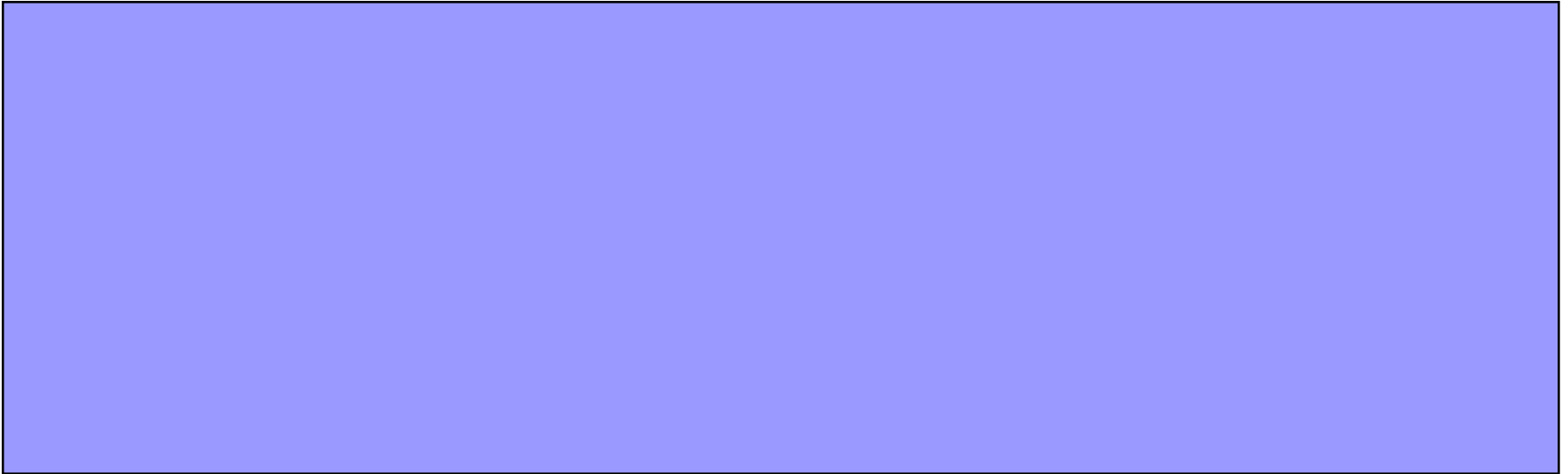


Switches

NMOS Pass Transistor—Passing 1

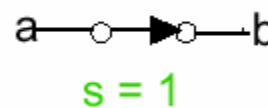
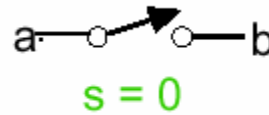
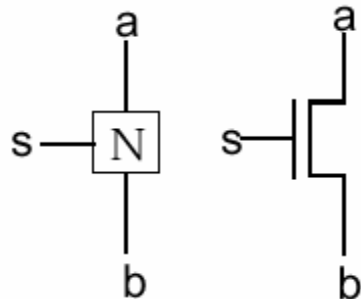


Threshold Drops



Switches

N- SWITCH



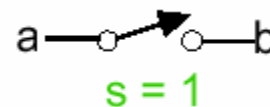
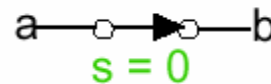
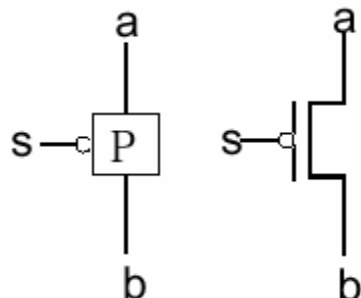
Input

Output

0 a ———> b Strong 0

1 a ———> b Weak 1

P- SWITCH



Input

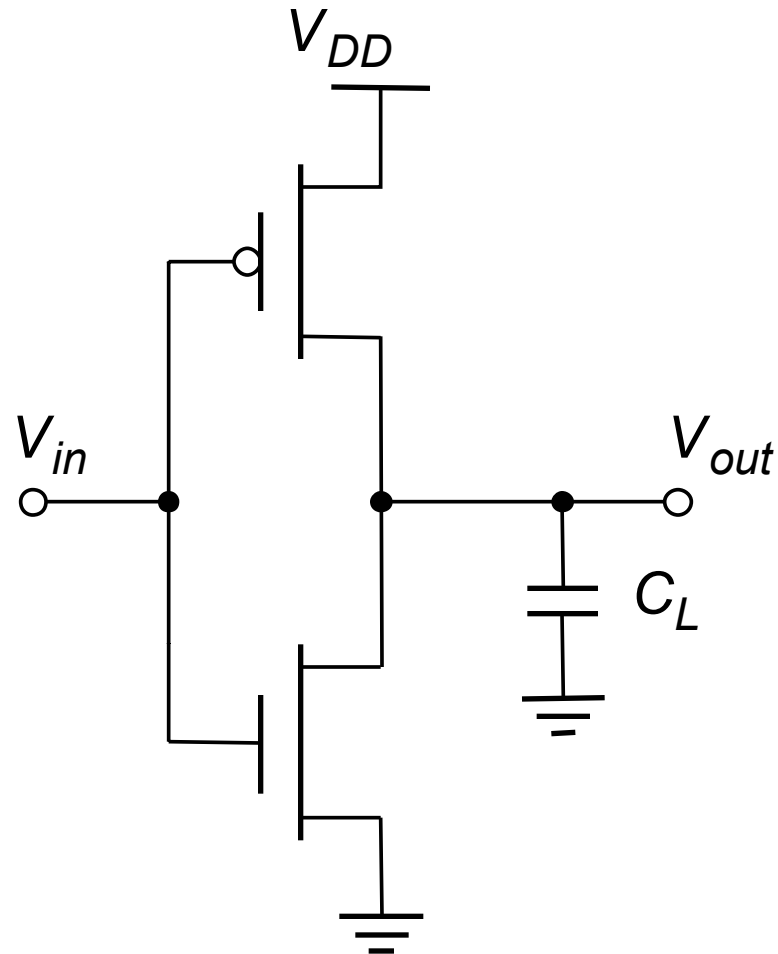
Output

0 a ———> b Weak 0

1 a ———> b Strong 1

El inversor

El inversor CMOS

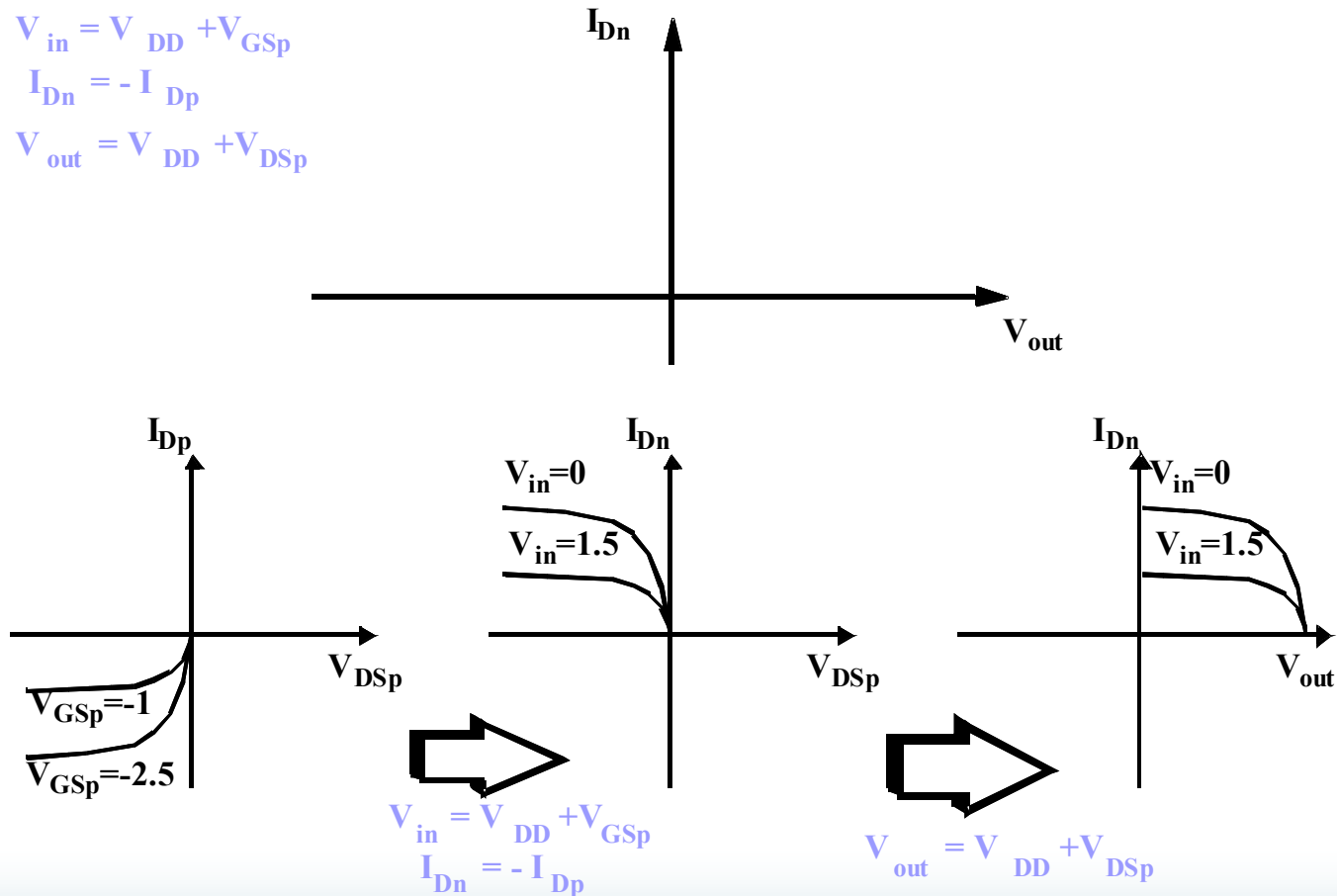


Rectas de carga de un PMOS

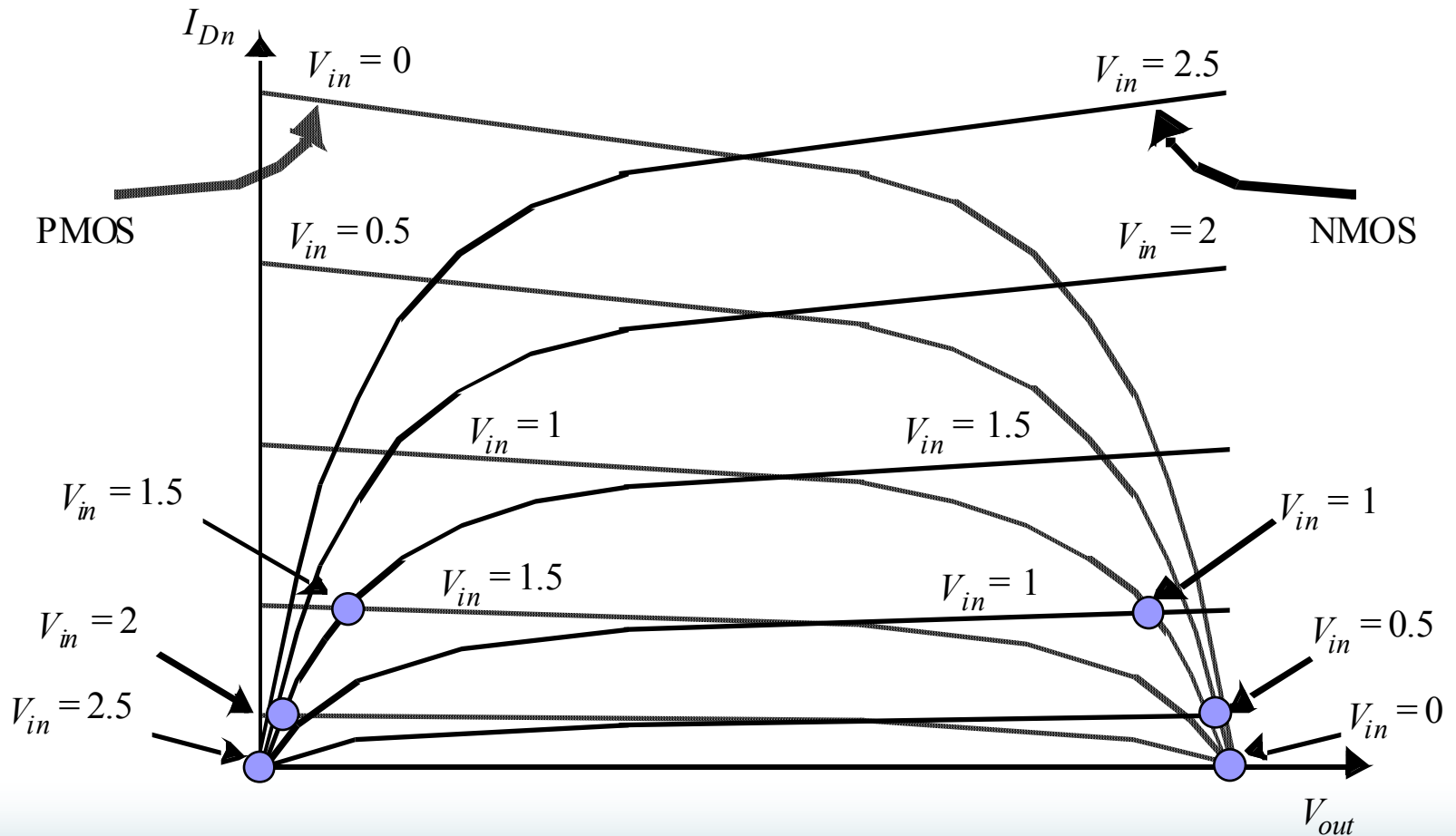
$$V_{in} = V_{DD} + V_{GSp}$$

$$I_{Dn} = -I_{Dp}$$

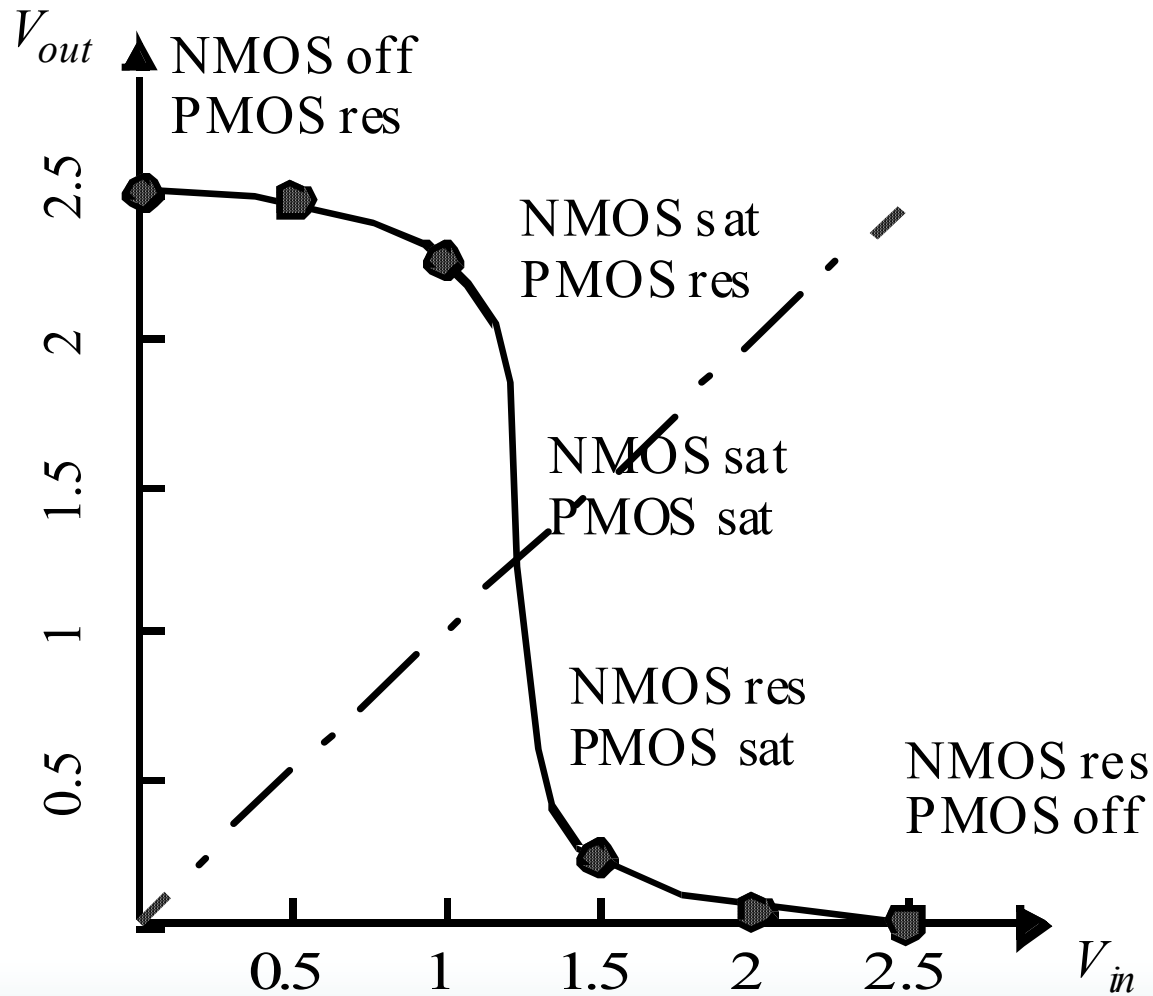
$$V_{out} = V_{DD} + V_{DSp}$$



CMOS Inverter Load Characteristics

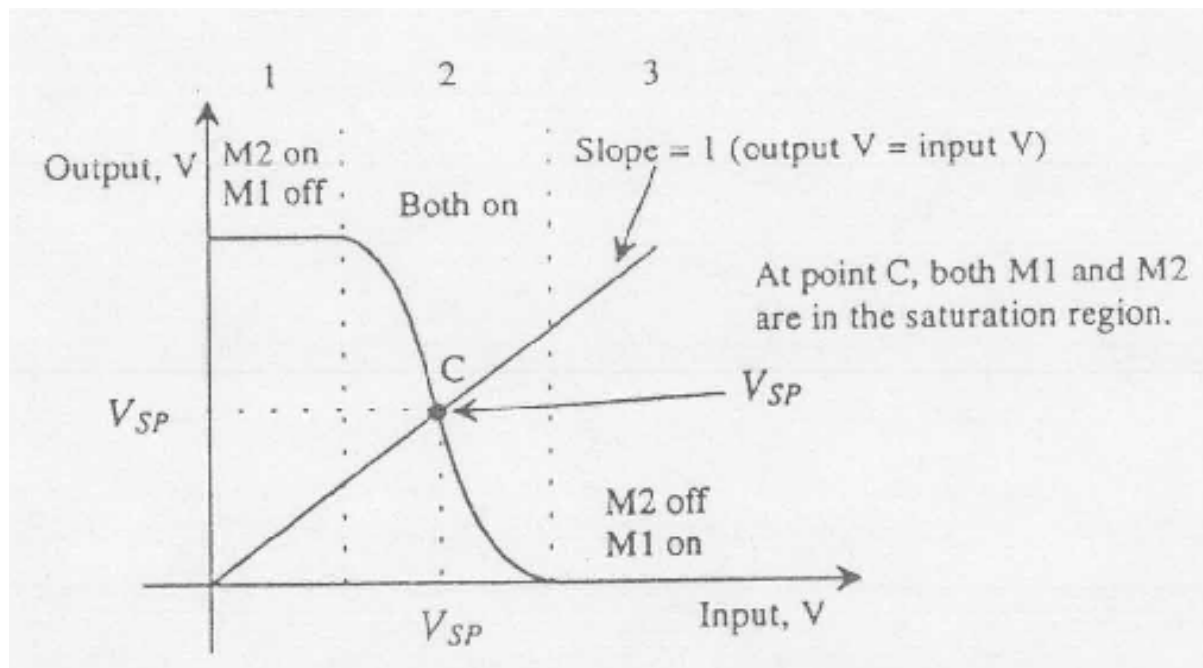


CMOS Inverter VTC



The Switching Threshold

- Switching threshold V_M is defined as the point where $V_{in} = V_{out}$



Switching Threshold as a function of Transistor Ratio

- Switching threshold V_M is defined as the point where $V_{in} = V_{out}$

$$K_n \frac{W_n}{L_n} (V_M - V_T)^2 = K_p \frac{W_p}{L_p} (V_{dd} - V_M - V_T)^2$$

- Yielding V_M as a function of transistor geometries, threshold voltages and Vdd

$$V_M = \frac{\sqrt{\beta_n / \beta_p} V_{Tn} + (V_{dd} - V_{Tp})}{1 + \sqrt{\beta_n / \beta_p}}$$

Transistor Ratio Setting

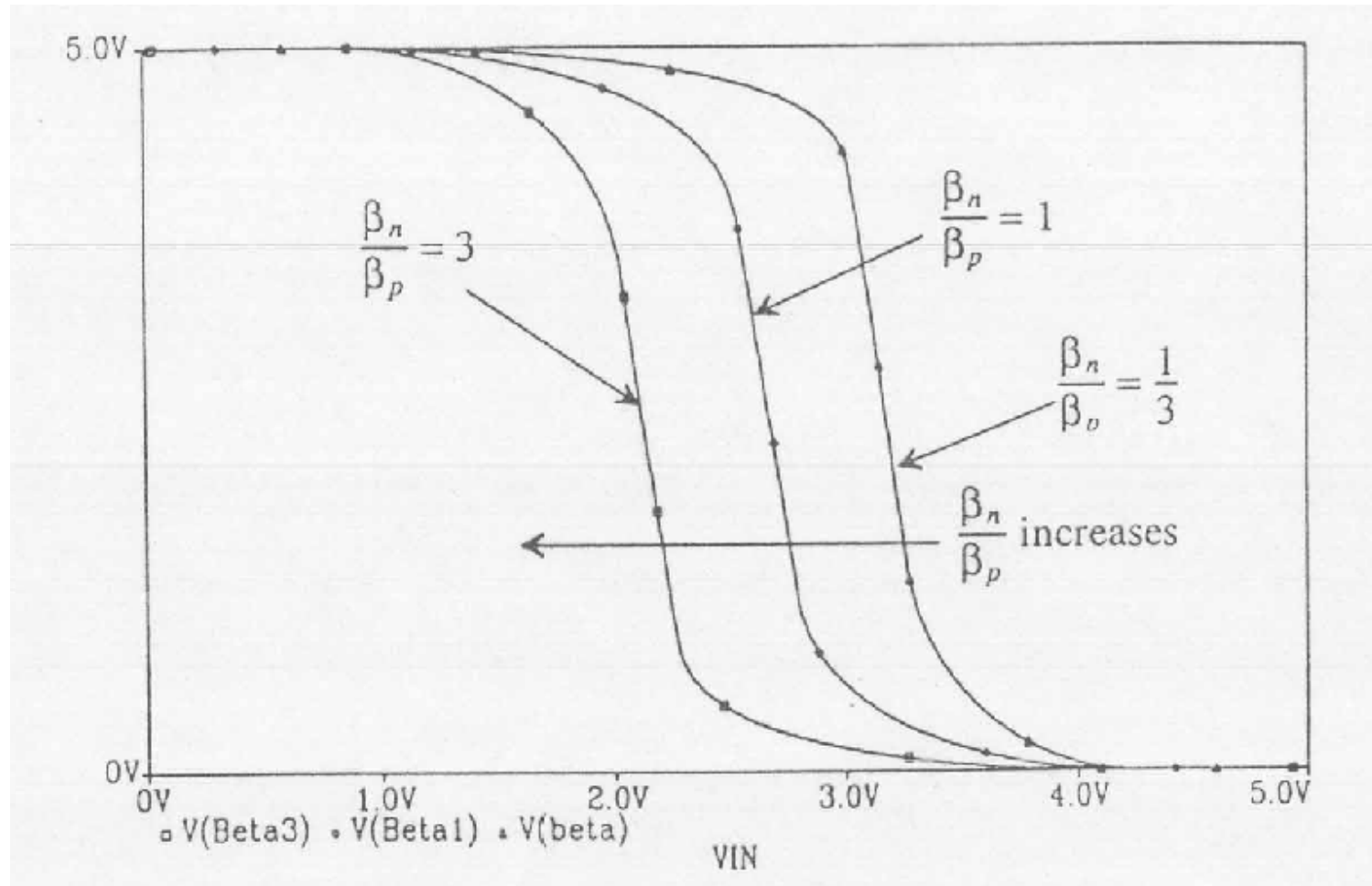
- With $V_M = V_{dd}/2$ the right hand side equals, in general to 1, so that

$$\frac{K_n S_n}{K_p S_p} = \frac{(V_{dd} - V_M - V_T)^2}{(V_M - V_T)^2}$$

$$\frac{S_n}{S_p} = \frac{K_p}{K_n}$$

- P transistor wider than N for equal margins

Switching Threshold



Power Dissipation

Where Does Power Go in CMOS?

- Dynamic Power Consumption

Charging and Discharging Capacitors

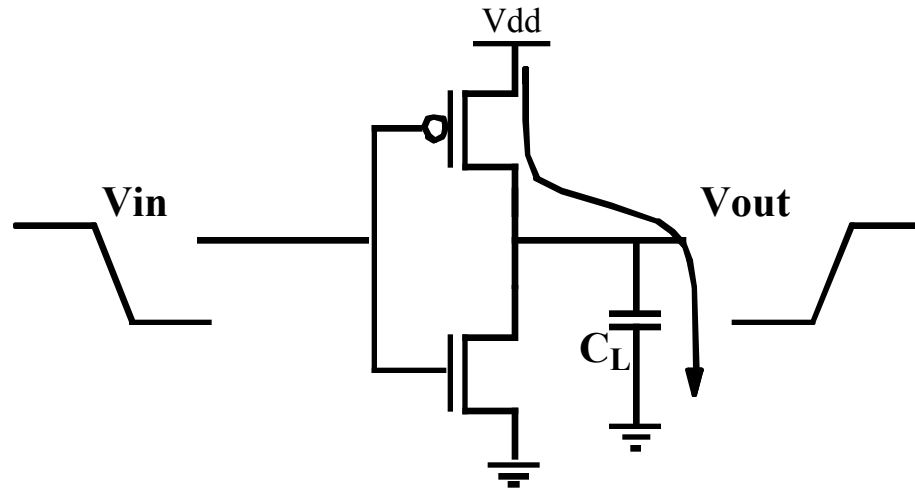
- Short Circuit Currents

Short Circuit Path between Supply Rails during Switching

- Leakage

Leaking diodes and transistors

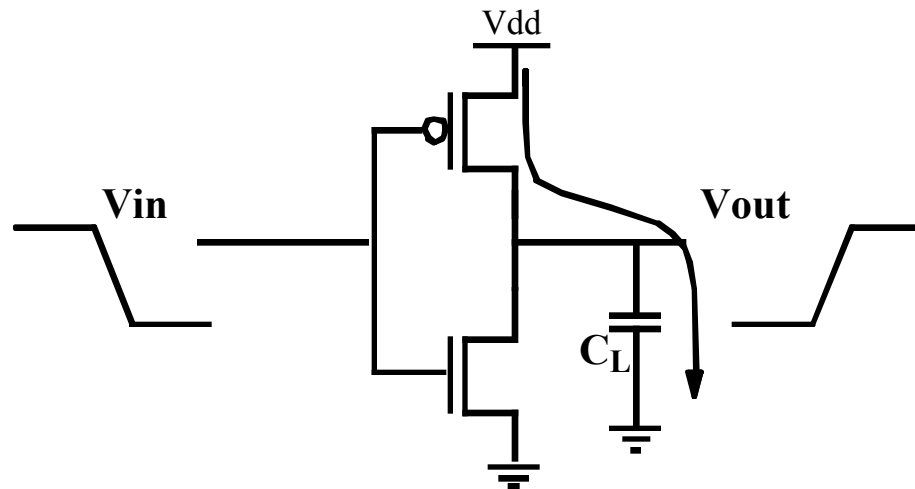
Dynamic Power Dissipation



$$E_{V_{dd}} = \int_0^{\infty} i_{V_{dd}}(t) V_{dd} dt = V_{dd} \int_0^{\infty} C_L \frac{dv_{out}}{dt} dt = C_L \int_0^{V_{dd}} dv_{out} = C_L V_{dd}^2$$

$$E_C = \int_0^{\infty} i_{V_{dd}}(t) v_{out} dt = \int_0^{\infty} C_L \frac{dv_{out}}{dt} v_{out} dt = C_L \int_0^{V_{dd}} v_{out} dv_{out} = \frac{C_L V_{dd}^2}{2}$$

Dynamic Power Dissipation



$$\text{Energy/transition} = C_L * V_{dd}^2$$

$$\text{Power} = \text{Energy/transition} * f = C_L * V_{dd}^2 * f$$

- Not a function of transistor sizes!
- Need to reduce C_L , V_{dd} , and f to reduce power.
- Dependence with supply voltage is quadratic !!!

Node Transition Activity and Power

- Consider switching a CMOS gate for N clock cycles

$$E_N = C_L \cdot V_{dd}^2 \cdot n(N)$$

E_N : the energy consumed for N clock cycles

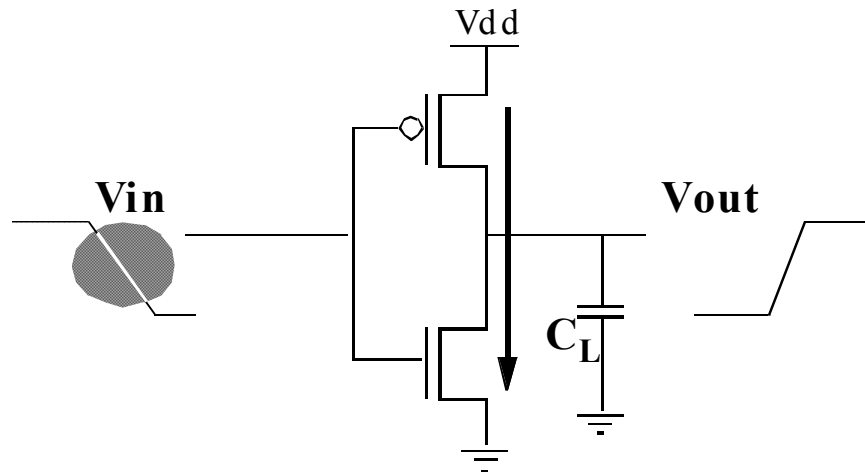
$n(N)$: the number of 0→1 transition in N clock cycles

$$P_{avg} = \lim_{N \rightarrow \infty} \frac{E_N}{N} \cdot f_{clk} = \left(\lim_{N \rightarrow \infty} \frac{n(N)}{N} \right) \cdot C_L \cdot V_{dd}^2 \cdot f_{clk}$$

$$\alpha_{0 \rightarrow 1} = \lim_{N \rightarrow \infty} \frac{n(N)}{N}$$

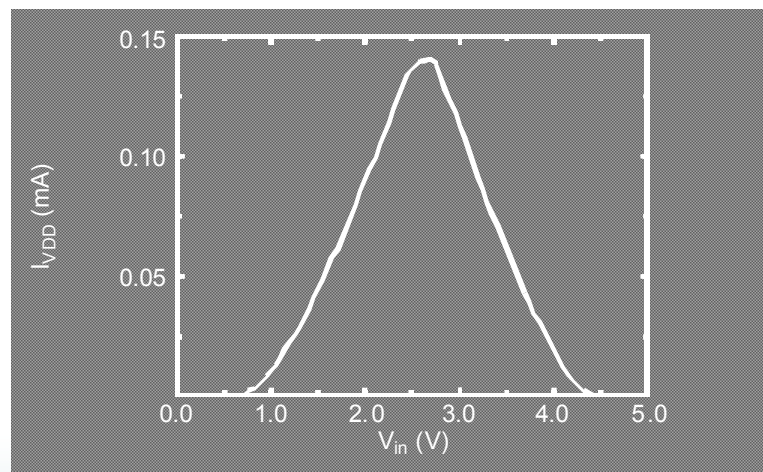
$$P_{avg} = \alpha_{0 \rightarrow 1} \cdot C_L \cdot V_{dd}^2 \cdot f_{clk}$$

Short Circuit Currents

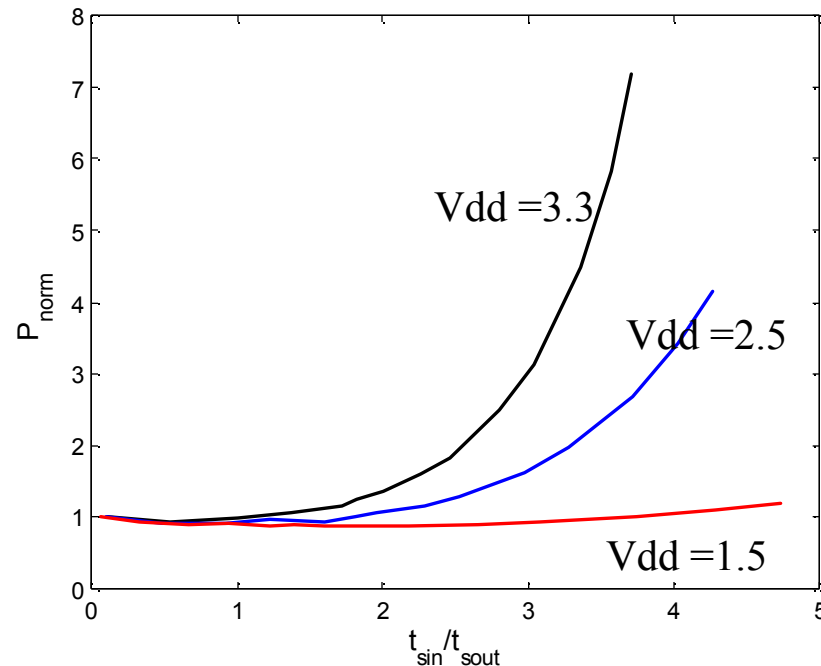


I_{peak} is a function of transistor sizes.

It is also a strong function of the input and output slopes ...

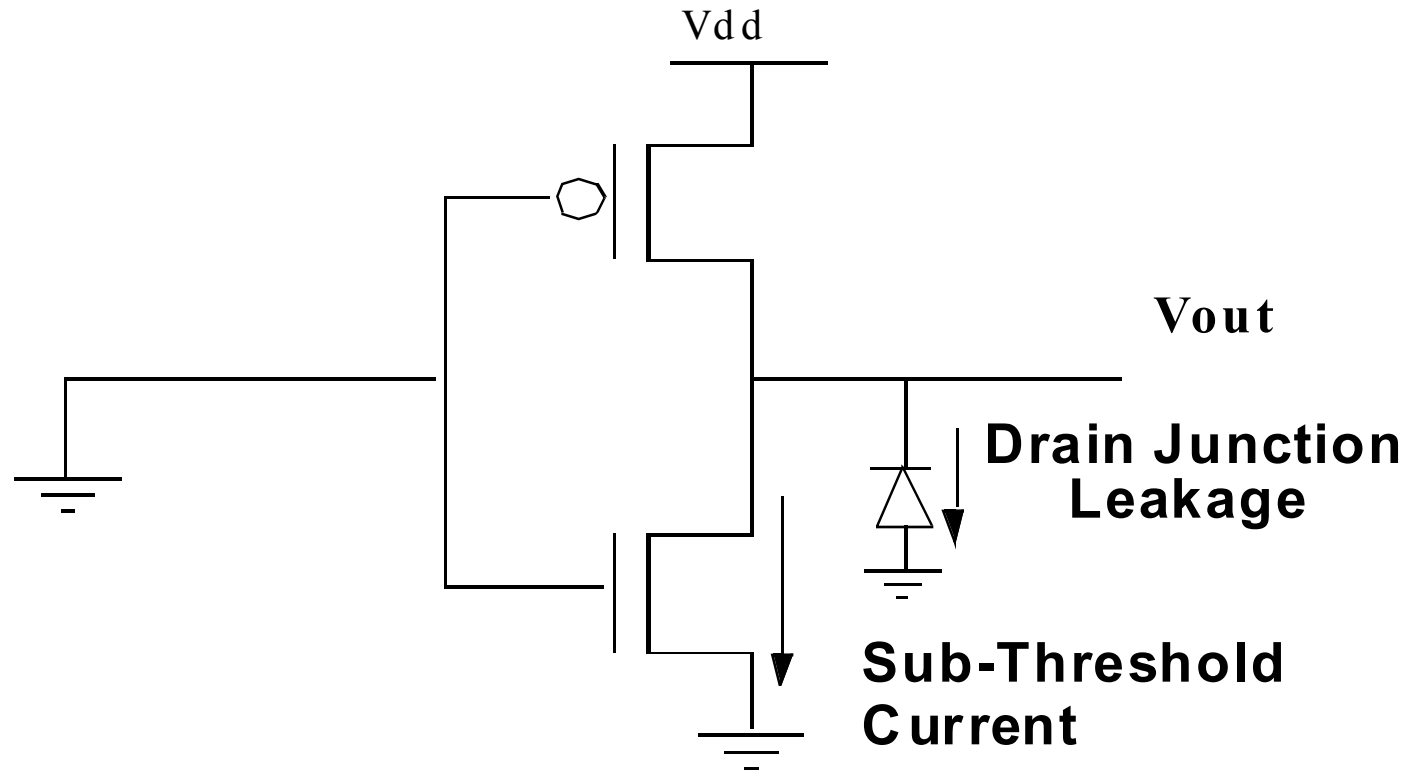


Minimizing Short-Circuit Power



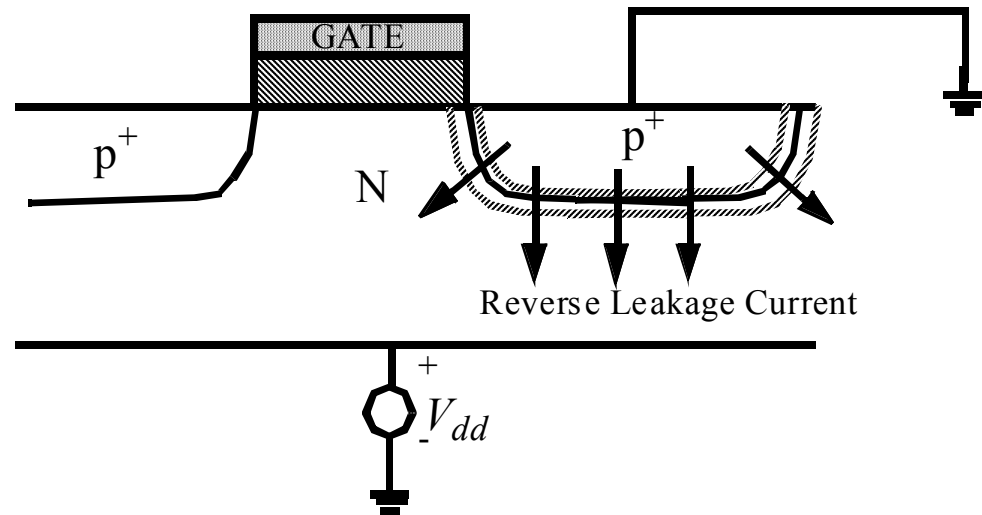
- Keep the input and output rise/fall times the same
($< 10\%$ of Total Consumption)
from [Veendrick84]
(*IEEE Journal of Solid-State Circuits*, August 1984)
- If $V_{\text{dd}} < V_{\text{tn}} + |V_{\text{tp}}|$ then short-circuit power can be *eliminated*!

Leakage



Sub-threshold current one of most compelling issues in low-energy circuit design!

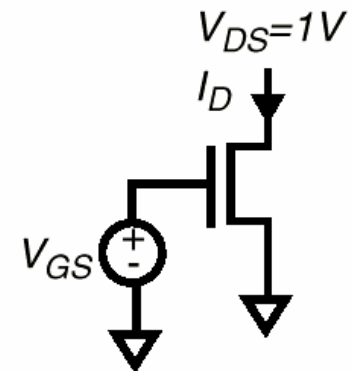
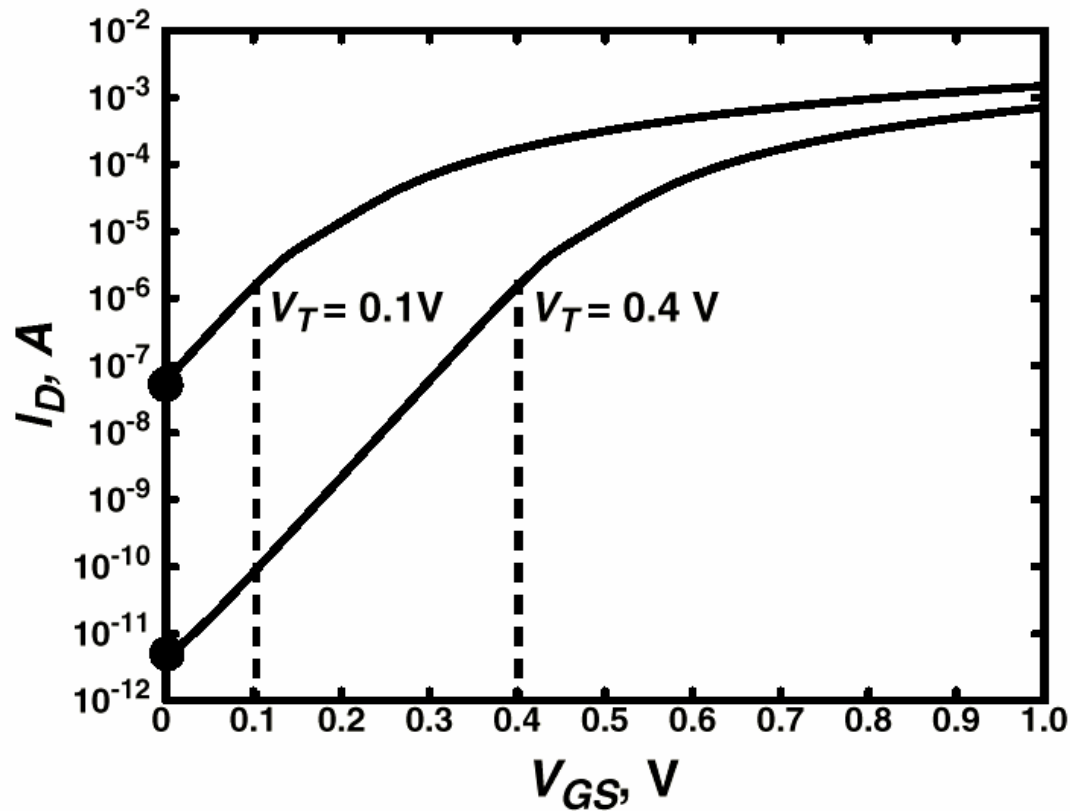
Reverse-Biased Diode Leakage



$$I_{DL} = J_S \times A$$

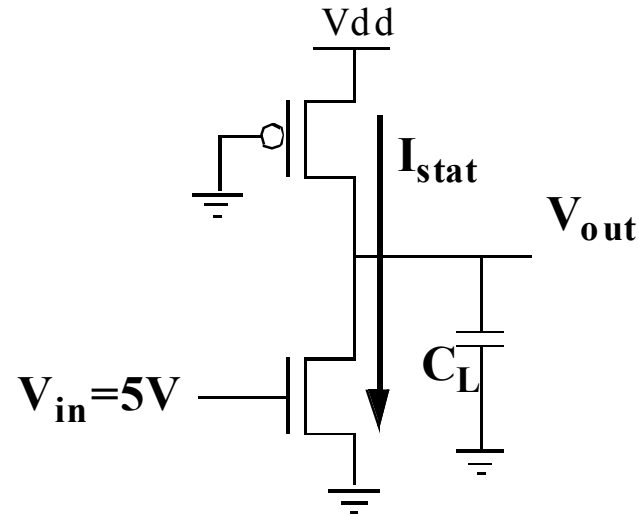
$J_S = 10\text{-}100 \text{ pA}/\mu\text{m}^2$ at 25 deg C for 0.25 μm CMOS
 J_S doubles for every 9 deg C!

Subthreshold Leakage Component



- Leakage control is critical for low-voltage operation

Static Power Consumption



$$P_{stat} = P_{(In=1)} \cdot V_{dd} \cdot I_{stat}$$

Wasted energy ...

Should be avoided in almost all cases,

but could help reducing energy in others (e.g. sense amps)

Principles for Power Reduction

- Prime choice: Reduce voltage!
 - Recent years have seen an acceleration in supply voltage reduction
 - Design at very low voltages still open question (0.6 ... 0.9 V by 2010!)
- Reduce switching activity
- Reduce physical capacitance

Background Material

- Semiconductor Physics and carrier modelling: Chapter 2, 3, Howe Sodini; Chapter 2, Robert Pierret.
- MOS modelling: Chapter 4, Howe Sodini; Chapter 16-18, Robert Pierret.

Apéndice

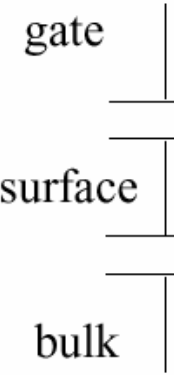
The capacitance

- Accumulation

$$C = C_{ox}$$

- Depletion

gate



Si/SiO₂ surface

bulk

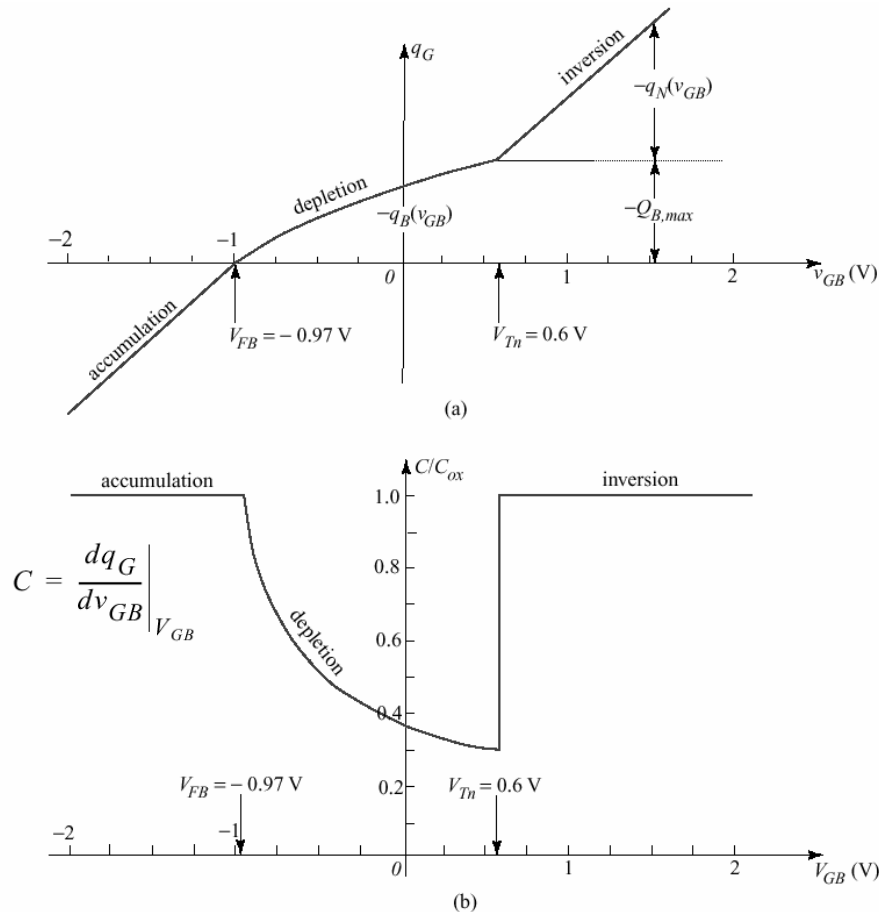
$$C_{ox} = \frac{\epsilon_{ox}}{t_{ox}}$$

$$C_b = \frac{\epsilon_s}{X_d}$$

$$C = C_{ox} || C_b$$

- Inversion

$$C = C_{ox}$$



Como accedemos localmente ?

- MOSIS (www.mosis.org)
- Precios de descuento para miembros de LACIS (bajo volumen):
 - 2.2mm x 2.2mm (AMI 1.5 μ m) 980US\$/4 =
246US\$ 5 unidades
 - 1.5mm x 1.5mm (AMI 0.5 μ m) 5000US\$/4 = 1250US\$ 5
unidades
- Mayores volúmenes implican menores costos